1/f Noise in Dye-sensitized Solar Cells and NIR Photon Detectors

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Dye-sensitized photon detector



Bonding of Dyes to the TiO₂ Surface



IR DYES



IR-1100



IR-1135

The problem of thick dye layers

Thick dye layers are insulating and also causes quenching, i.e., $D^* + D^* - - \rightarrow D + D + heat$ $D^* + D - - - \rightarrow D + D + heat$

Semiconductor Dye Monolayer

At monolayer coverage quantum and energy conversion efficiencies are very small because of the poor light absorption by the monolayer.

To increase the photon absorption cross-section dye is deposited on the rough electron conducting surface

Hole Collector (Redox electrolyte or p-type



→Pt



TiO₂(dyed) Conducting Tin Oxide

hν

Thickness of the light absorbing layer can be made smaller than the exciton or carrier diffusion length $L=(D\tau)^{1/2}$, while maintaining a large optical absorption cross-section



Light absorbing material- dye, semiconductor, Q-dots

Efficiencies (E &Q) of dyesensitized solar cells

Cells based on electrolytes ~ E~ 10%, Q~ 85% Fully solid state cells (solid hole collector) ~ E ~ 4%, Q ~ 60% **Recombination Modes: Dye Sensitized Solar Cells/Photon Detectors**

1.Geminate recombination $hv + D \rightarrow D^* \rightarrow D^+ + e^ D^+ + e^- \rightarrow D$

- 2. Recombination of the injected electron with an acceptor at dyed oxide surface
- 3. Recombination of the injected electron with an acceptor at the exposed conducting glass surface.

Injection and Geminate Recombination Rates

Injection time $\mathbf{D}^* \rightarrow \mathbf{D}^+ + \mathbf{e}^-, 10^{-14} - 10^{-15}\mathbf{s}$

k = $4\pi^2/h [\langle i|H|j \rangle]^2 \rho(E)$? H = Semicoductor-Dye Electronic Coupling $\rho(E) =$ Density of States in the CB Recombination time $D^+ + e^- \rightarrow D$, $10^{-5} - 10^{-7}s$ Recombination of Electrons with Acceptors During Transit



Recombination rate =κ

Recombination Time $=\kappa^{-1}=\tau$

Mean free path = $(D\tau)^{1/2}$



Recombination after leakage from the nanoparticle surface Recombination at the back contact



Surface trap mediated recombination

Problem of Surface Traps

- 1. Surface trap mediated recombination is very severe
- 2. Trapping and detrapping slows down transport (reduces diffusion coefficient)
- **3. Trapping/Detrapping generate noise**



Recombination of Electrons with Acceptors During Transit



Recombinations are generally mediated by surface states

Recombination Rate ~ (Ψ_s, Ψ_b)

We are not certain whether Ψ_b the wave function of electron in the bulk of the semiconductor is conduction band state or a trapped state

1/f Noise in Mesoscopic Semiconductor films

At constant voltage ,current exhibits 1/f (f=frequency)noise

This noise is quite sensitive to trappingdetrapping of carriers The fluctuating current is of the form

 $I(t) = I_0 + X(t) \text{ where } I_0 \text{ is the mean and we}$ define S(f) as

$$S(f) = Lim_{T \to \infty} \left(\frac{1}{2T} \left| \int_{-T}^{T} X(t) e^{-2\pi i f t} dt \right|^2 \right)$$

S(f) gives the noise power spectrum as a function of f

A schematic diagram illustrating (a) sample geometry used for the noise measurement. (b) The circuit used for the noise measurement.



S(f) generally satisfy Hoog's Formula



The constant A measures the level of noise and δ is an exponent close to unity.

Noise spectra at 23°C of, (a) bare TiO2 film in N2. (b) bare TiO2 film in N2 at RH \sim 70 %. (c) bare TiO2 in a N2 saturated with I2 vapor. (d) TiO2/BPR in N2. (e) TiO2/N3 in N2. (f) TiO2/BPR in N2 saturated with I2. (g) TiO2/N3 in N2 saturated with I2. (h) TiO2/BPR in N2 at RH \sim 70 %. (i) TiO2/N3 in N2 at RH \sim 70%.



The values of parameters A and δ for different systems obtained by fitting noise data to the formulae (1),

biasing voltage = 18 V :	$I_o = 3.2 \times 1$	$I_o = 3.2 \times 10^{-4} \text{ A}.$	
sample	δ	A	
TiO ₂ (vacuum)	0	4.4×10 ⁻¹⁸	
$TiO_2(N_2)$	0	4.4×10 ⁻¹⁸	
TiO ₂ /BPR (vacuum)	0	4.4×10 ⁻¹⁸	
TiO ₂ /N3 (vacuum)	0.	4.4×10 ⁻¹⁸	
TiO ₂ /BPR (N ₂)	0	4.4×10 ⁻¹⁸	
$TiO_2/N3 (N_2)$	0	4.4×10 ⁻¹⁸	
$TiO_2(N_2, RH = 70\%)$	1.25	8.8×10 ⁻¹⁰	
TiO ₂ /BPR (N ₂ , RH= 70%)	1.15	4.4×10 ⁻¹¹	
TiO ₂ /N3 (N ₂ , RH = 70%)	1.30	5.7×10 ⁻¹⁰	
TiO_2 (N ₂ , saturated I ₂ vapor)	1.37	5.8×10 ⁻⁹	
$\rm TiO_2/\rm BPR$ ($\rm N_2$, saturated $\rm I_2$ vapor)	0	4.3×10 ⁻¹⁸	
TiO ₂ /N3 (N_2 , saturated I_2 vapor)	0	4.4×10 ⁻¹⁸	

Results of the Noise Measurement

- 1. TiO₂ film in vacuum or N_2 no 1/f noise
- $2.TiO_2$ film in N₂ with traces of I₂ intense 1/f noise
- 3. Dyed TiO_2 film in N_2 with iodine no 1/f noise

Electron acceptor states created by adsorbed iodine creates 1/f noise. The dye passivates acceptor states. When the nanocrystalline surface is bonded with a suitable dye, the trapping sites are passivated.
1/f noise suppressed
Recombination suppressed
Electron transport facilitated (D_{dye}>> D_{bare})

Recombination in Dye-sensitized Devices

Surface traps that generate 1/f noise are also the recombination sites.

Conclusion from Noise Experiments

Nanocrystalline oxide films are heavily populated with defects, surface states ,adsorbed species etc, that act as trapping (recombination) sites. Passivation by dye adsorption clears most of these traps. Possible applications – Solar Cells, Photon Detectors.

Dye-sensitized NIR detector



Response time $\tau \sim L^2/D$ L= Film thickness, D = Diffusion coefficient

Detectivity ~ 10^{11} cm Hz^{-1/2}W⁻¹ (812 nm)

Detectivities of the same order for some dyes absorbing in the region 1000 nm Responsitivities are rather low ~ 10⁻³ A/W

Strategies for improvement

Design dyes to achieve the following

- 1. Peak absorption
- 2. Fast injection slow geminate recombination
- 3. Attach ligands to passivate trapping sites

Conclusion

High band-gap mesoscopic semiconductors

Insensitive to visible/IR
Slow carrier transport
Noise
Recombination of photogenerated carriers

All the above ills can be cured in one stroke by
bonding the surface with a suitably designed dye

Cells based on Indoline Dyes

Indoline organic dyes give high conversion efficiencies ?

Understanding of their properties and mode of interaction with TiO₂ likely to give very important clues

Structural Formula of the Indoline dyes D-149 and D-102







The Secret of Indolines?

Anchorage via carboxylate ligand facilitate electron injection.

It seems that basic nitrogen sites in indoline passivates electron accepting acidic sites on TiO₂. Thus recombination and noise suppressed.

Indoline like structures can be made to absorb in the NIR region

Photocurrent Action spectra of SnO2 cells sensitized with(a) D-149and(b) D-102



I-V Characteristics of SnO₂ cells sensitized with (a) D-149 (b) D-102 and (c) N719 and Dark I-V Characteristics of SnO2 cells sensitized with (d) D-149 (e) D-102 and (f) N719



V / mV

I-V Parameters of SnO₂ cells sensitized with indoline and Rubipyridyl dyes

Dye	J _{sc} mAcm ⁻²	V _{oc} mV	η %	FF
D-149	14.1	409	2.8	0.49
D-102	11.9	380	2.2	0.50
N-719	12.1	262	1.2	0.37

Indoline vs Ru dyes on SnO₂

SnO₂ based dye-sensitized cells are more susceptible to recombination than TiO₂ cells.

With SnO₂ indolines give efficiencies higher than that Ru bipyridyl dyes

It seems that indoline dyes passivates SnO₂ surface more effectively closing the recombination sites

Dye-sensitized NIR Detector



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